

# EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

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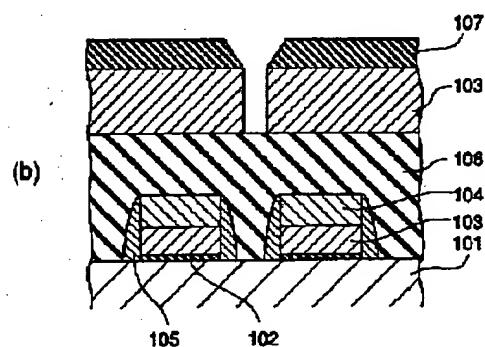
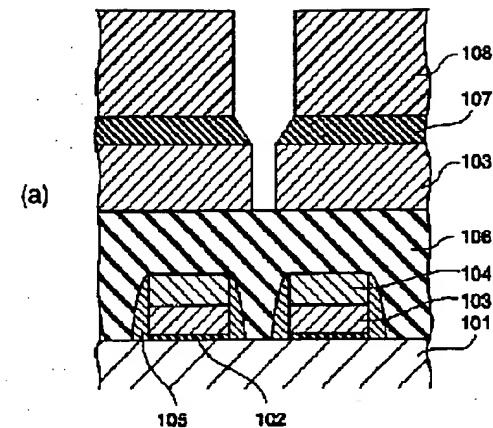
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TITLE : FORMATION OF FINE CONNECTION  
HOLE



ABSTRACT : PROBLEM TO BE SOLVED: To provide a novel method for forming a fine connection hole which obtains a stable opening characteristic, while suppressing the increase of opening diameter in a mask.

SOLUTION: A mask layer 103 is formed on a substrate 101, having a film for forming the fine connection hole. A antireflection film 107 is formed on the mask layer 103. A hole, having a diameter decreasing toward the substrate 101 side, is formed in the antireflection film 107. A pattern for forming a fine connection hole is formed in the mask layer 103, using the reflection preventing film 107 having a hole. The fine connection hole is formed in the film, in accordance with the pattern for forming the fine connection hole.

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